

Title (en)

Ink composition, injet recording method, printed material, and process for producing lithographic printing plate

Title (de)

Tintenzusammensetzung, Tintenstrahlaufzeichnungsverfahren, Druckmaterial und Verfahren zur Herstellung einer Lithographiedruckplatte

Title (fr)

Composition d'encre, procédé d'enregistrement de jet d'encre, matériau d'impression, et procédé de production de plaque d'impression lithographique

Publication

**EP 1975213 A1 20081001 (EN)**

Application

**EP 08009928 A 20070703**

Priority

- EP 07013001 A 20070703
- JP 2006183513 A 20060703
- JP 2006225105 A 20060822
- JP 2006309285 A 20061115

Abstract (en)

An ink composition is provided that includes (A) an N-vinylactam, (B) a monomer represented by Formula (I), and (C) a radical polymerization initiator, or includes (A) an N-vinylactam, (B) a monomer represented by Formula (II), (C) a radical polymerization initiator, and phenoxyethyl acrylate. (In Formula (I) and Formula (II), R 1 denotes a hydrogen atom, a halogen atom, or an alkyl group having 1 to 4 carbons, X 1 denotes a divalent linking group, R 2 and R 3 independently denote a substituent, k denotes an integer of 1 to 6, q and r independently denote an integer of 0 to 5, n denotes a cyclic hydrocarbon structure, the cyclic hydrocarbon structure may comprise in addition to hydrocarbon bonds a carbonyl bond (-C(O)-) and/or an ester bond (-C(O)O-), and the k R 1 s, the k X 1 s, the q R 2 s, and the r R 3 s may each be identical to or different from each other; furthermore, one carbon atom in the adamantane framework in Formula (I) may be replaced by a carbonyl bond (-C(O)-) and/or an ester bond (-C(O)O-), and one carbon atom in the norbornene framework in Formula (II) may be replaced by an ether bond (-O-) and/or an ester bond (-C(O)O-).) There are also provided an inkjet recording method, a printed material, and a process for producing a lithographic printing plate that employ the ink composition.

IPC 8 full level

**B41C 1/10** (2006.01); **B41J 2/01** (2006.01); **B41M 5/00** (2006.01); **C09D 11/00** (2014.01); **C09D 11/322** (2014.01); **C09D 11/328** (2014.01)

CPC (source: EP US)

**B41C 1/1066** (2013.01 - EP US); **C09D 11/101** (2013.01 - EP US); **C09D 11/36** (2013.01 - EP US); **Y10S 430/117** (2013.01 - EP US)

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#### Designated contracting state (EPC)

AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HU IE IS IT LI LT LU LV MC MT NL PL PT RO SE SI SK TR

#### Designated extension state (EPC)

AL BA HR MK RS

#### DOCDB simple family (publication)

**EP 1876209 A1 20080109; EP 1876209 B1 20121031**; EP 1975213 A1 20081001; EP 1975213 B1 20130327; JP 2008075062 A 20080403; JP 5276264 B2 20130828; US 2008008966 A1 20080110; US 7553605 B2 20090630

#### DOCDB simple family (application)

**EP 07013001 A 20070703**; EP 08009928 A 20070703; JP 2006309285 A 20061115; US 82206107 A 20070702